



Development of Metallic Magnetic Calorimeter Arrays with Embedded ^{163}Ho for the ECHo Experiment

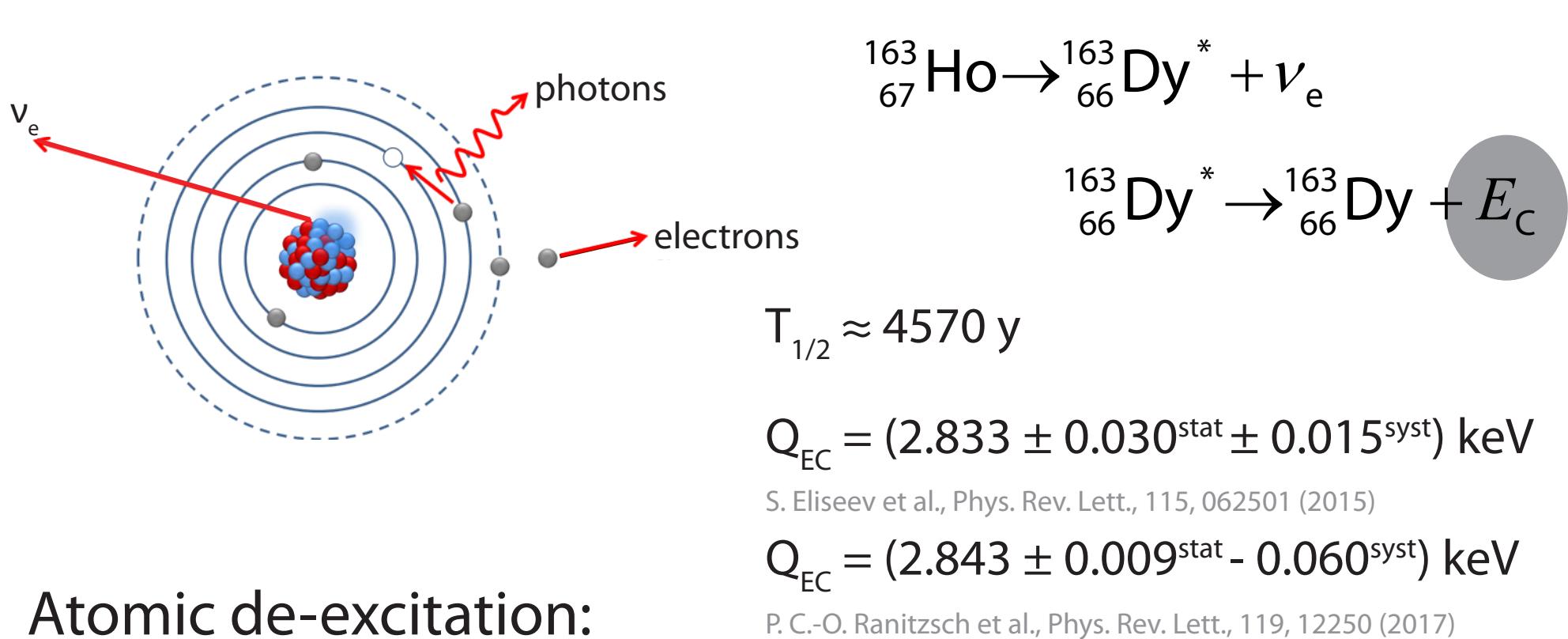
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The ECHo Experiment

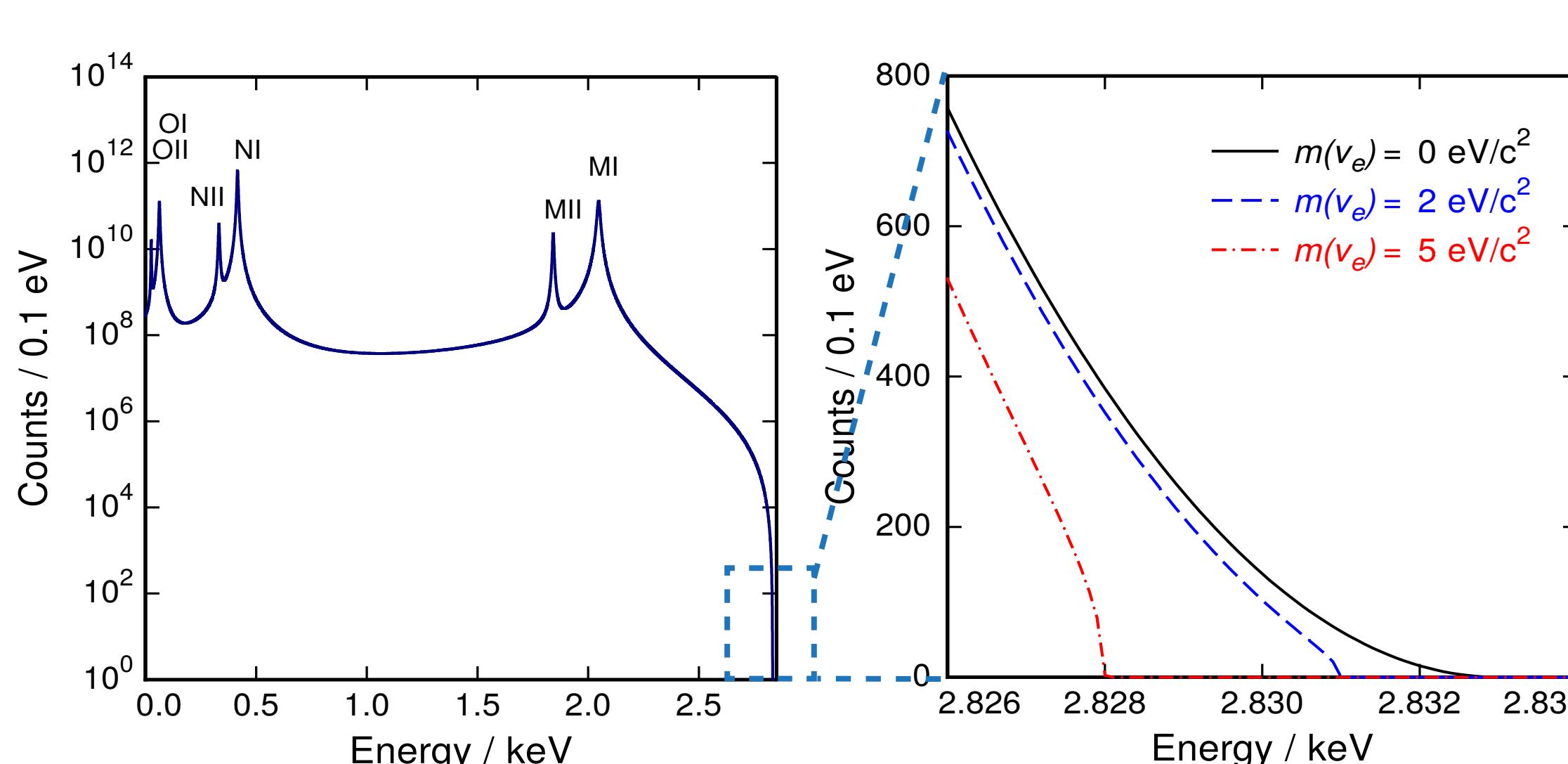
Electron capture of ^{163}Ho



Atomic de-excitation:

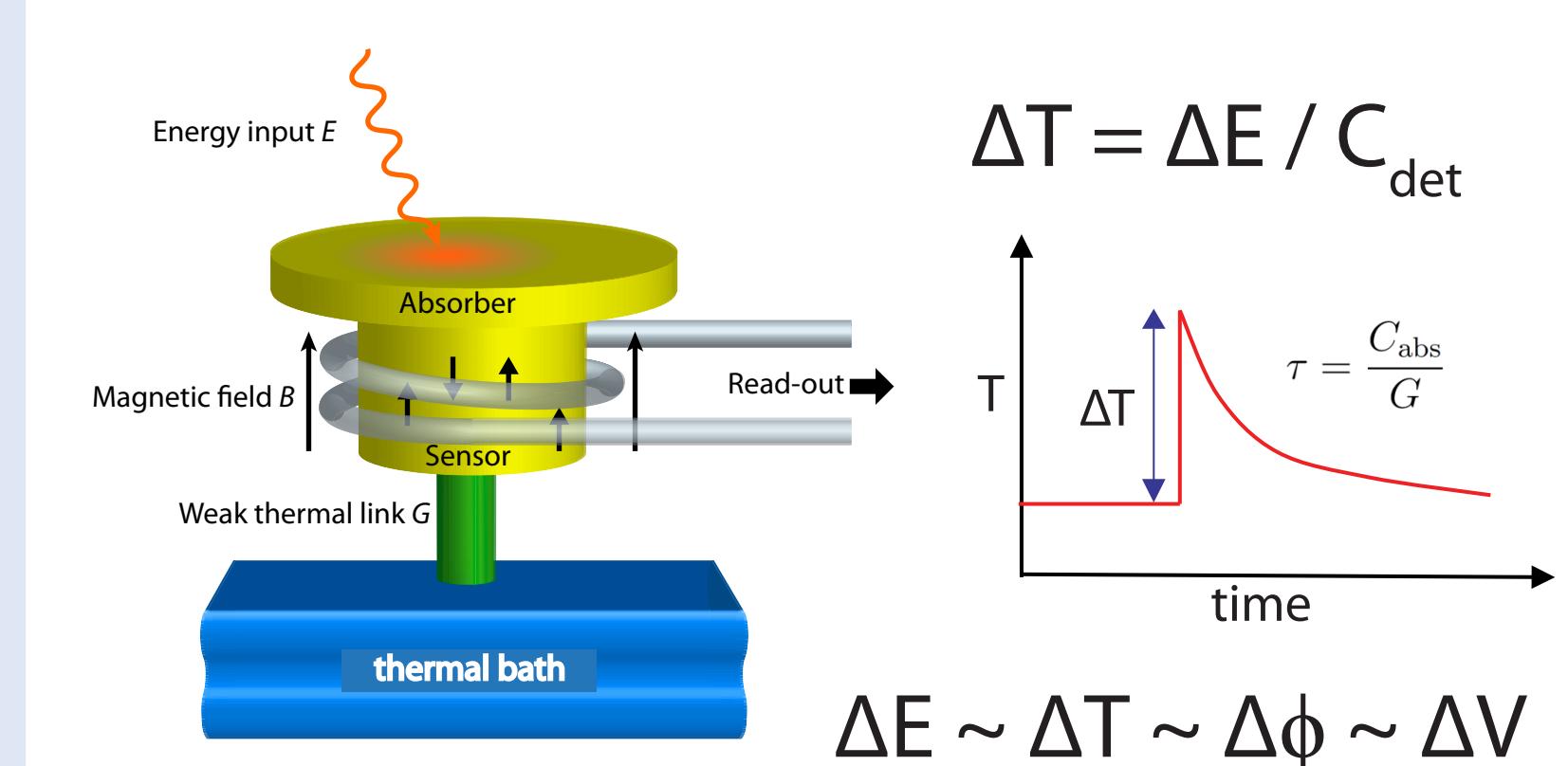
- X-ray emission
 - Auger electrons
 - Coster-Kronig transitions
- Calorimetric measurement

^{163}Ho calorimetrically measured spectrum



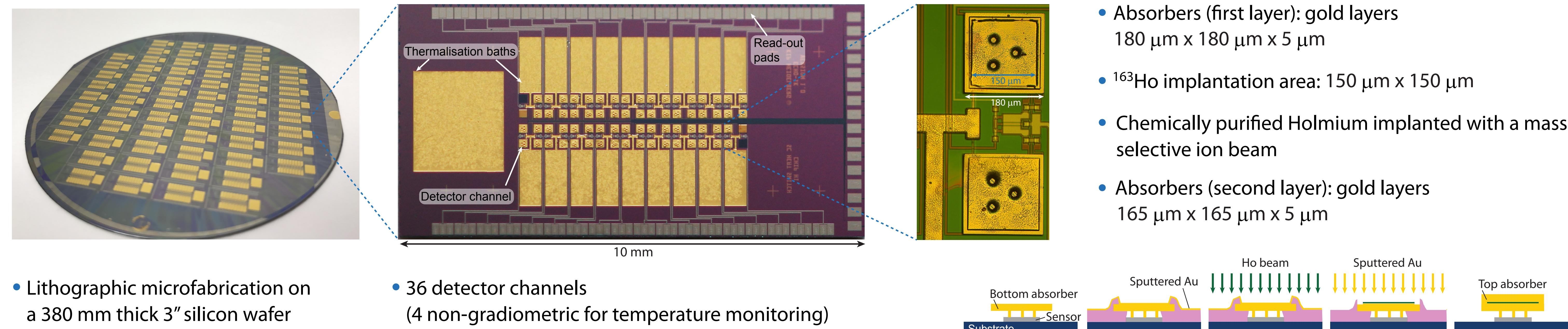
MMC Working Principle

Metallic magnetic calorimeter (MMC)



Detector Layout and Implantation

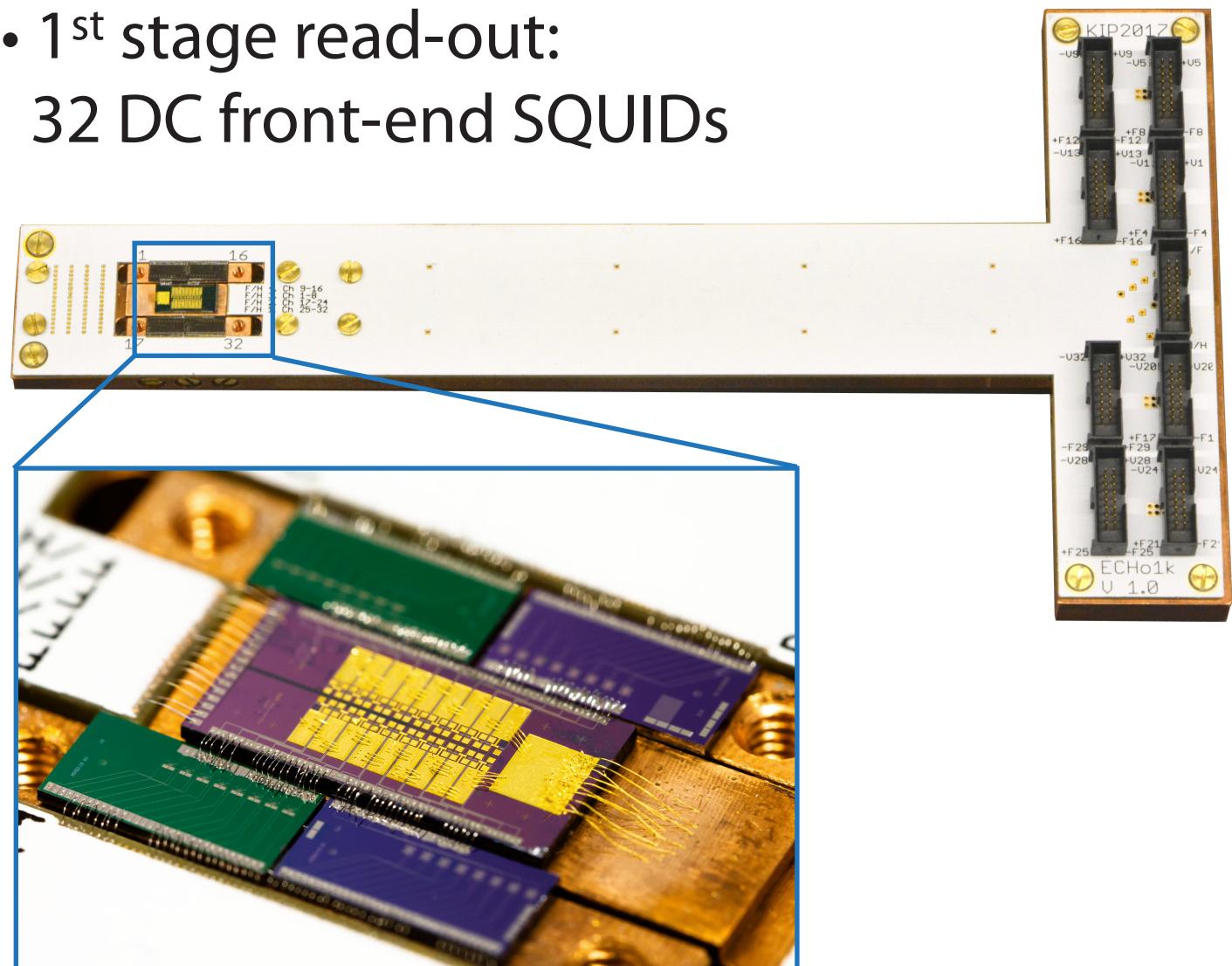
ECHo-1k detector chip: 64-pixels MMC array for implantation with ^{163}Ho



Cryogenic Set-up and Detector Characterisation

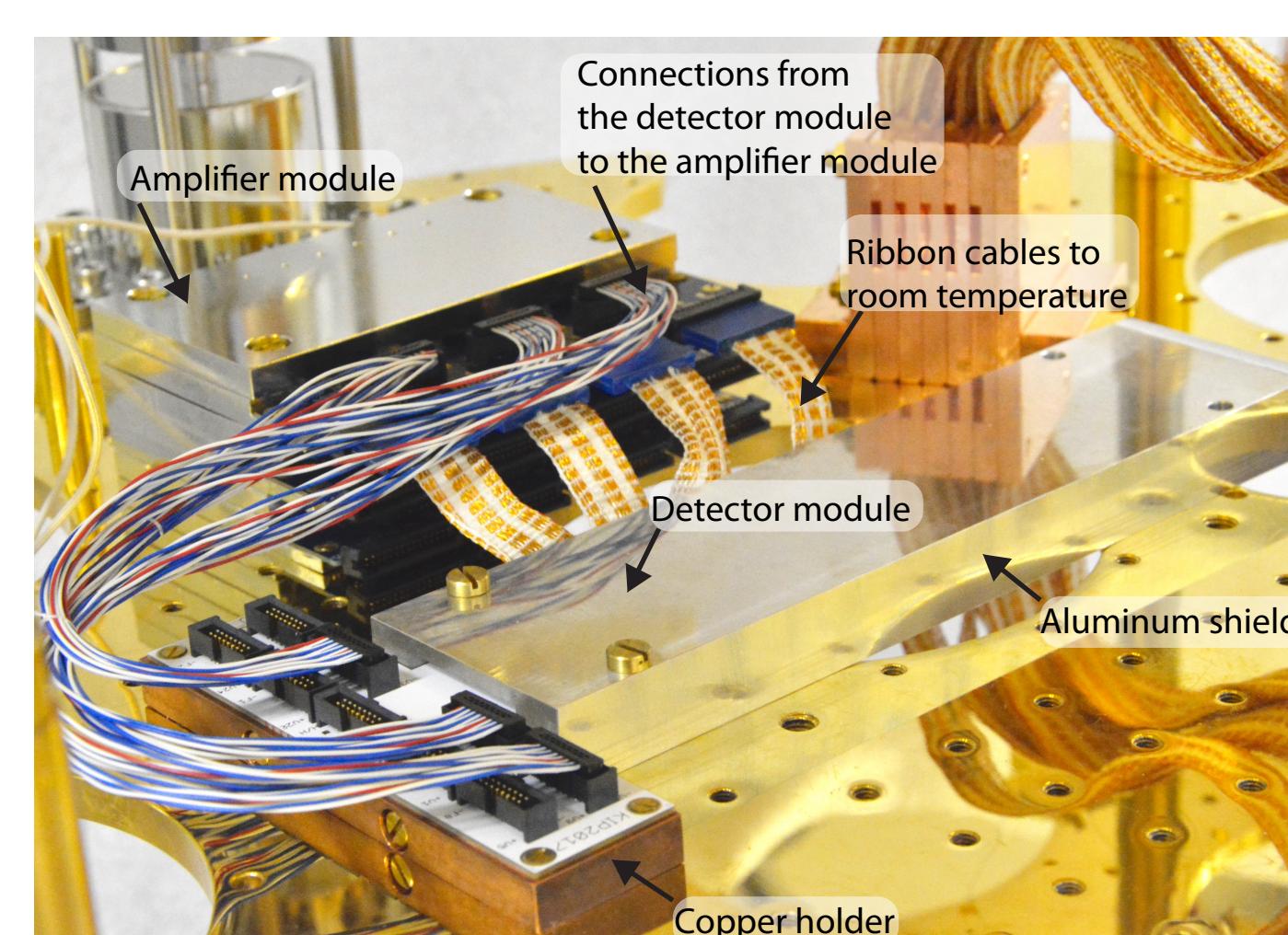
Detector platform

- Copper holder → good thermalisation
- Dedicated circuit board
- Gold bondings to ensure detector thermalisation
- 1st stage read-out: 32 DC front-end SQUIDs



Full mounted set-up

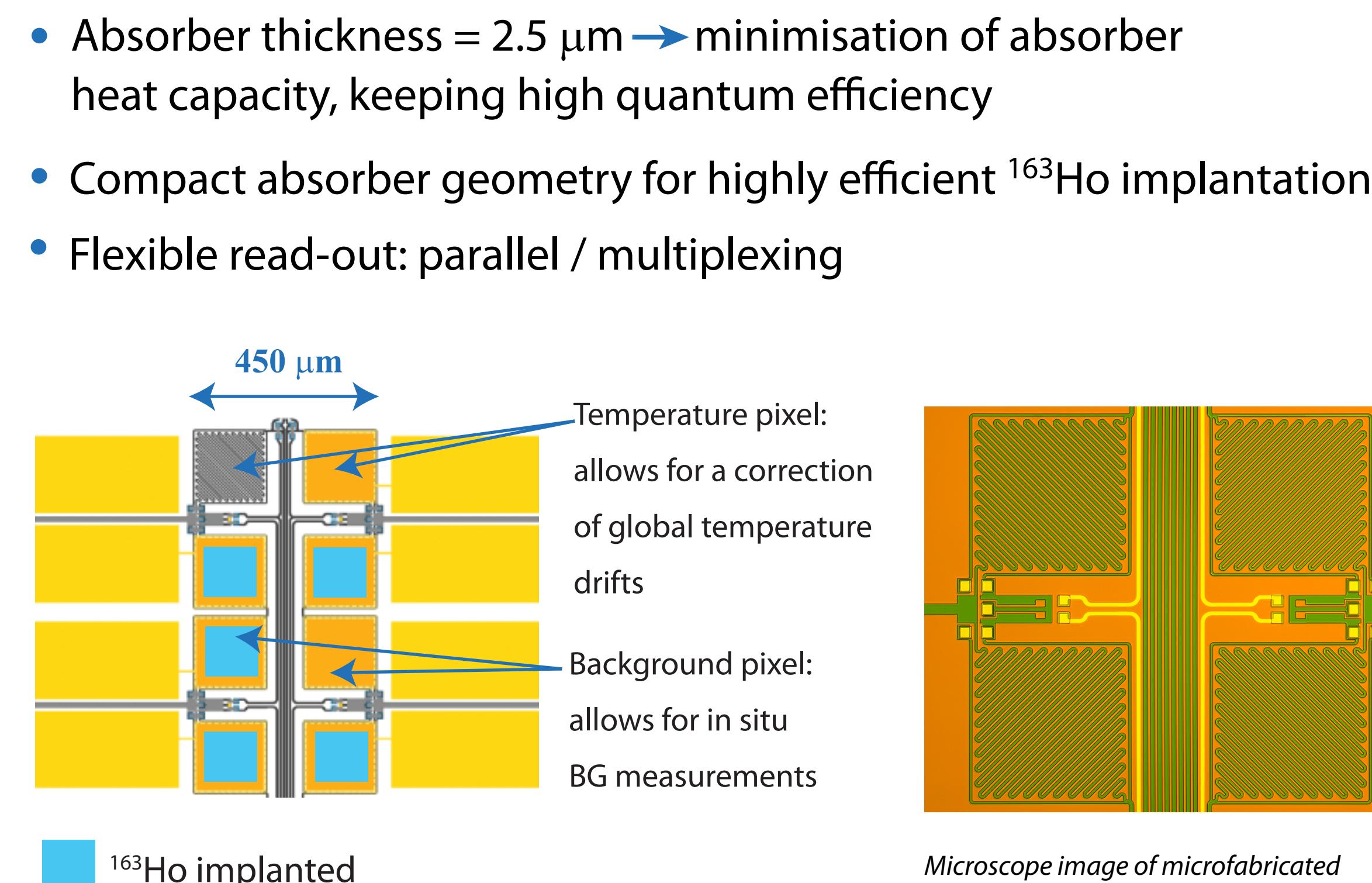
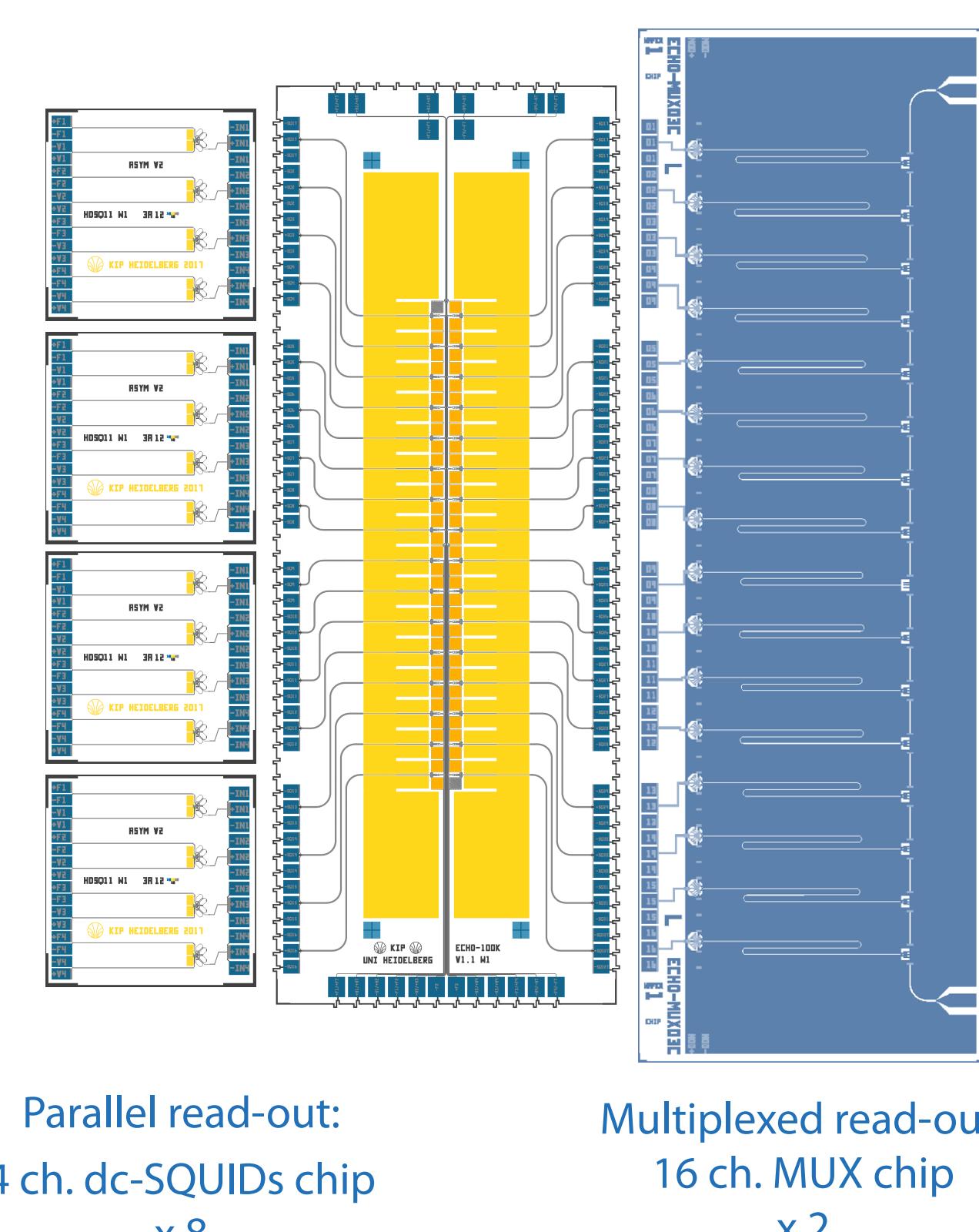
- 32 channels for parallel read out
- Mounted at the cryostat mixing chamber plate ($T \approx 8 \text{ mK}$)
- T-shaped copper holder with aluminium shielding against external magnetic fields



System characterisation

- Activity per pixel: average activity = 1.06 Bq / pixel
- Energy resolution: $\Delta E_{\text{FWHM}} @ 0.41 \text{ keV}$ (NI line) between 6.0 eV and 7.7 eV
- Total background: $< 1.6 \cdot 10^{-6} \text{ events/eV/det/day}$

New Detector Design



Summary and Outlook

- ECHo 1st generation MMC arrays were successfully produced and tested
- implanted with ^{163}Ho source
- New design for next generation MMC arrays for ECHo has been developed and it's currently being produced

Next steps:

- characterisation of new design at mK temperatures
- ^{163}Ho implantation on wafer scale
- characterisation of different ^{163}Ho implantation concentrations
- characterisation of different host materials for implantation